## What is claimed is:

1. A photoimageable composition comprising a photoactive component and a polymer component,

the polymer component comprising a fluorinated polymer that comprises Si atoms and silanol groups,

wherein the polymer has a ratio of fluorine atoms to Si atoms of about 3 or less.

- 2. The photoimageable composition of claim 1 wherein the polymer has a ratio of fluorine atoms to silicon atoms of about 2 or less.
  - 3. The photoimageable composition of claim 1 wherein the polymer comprises at least three distinct repeat units.
- 15 4. The photoimageable composition of claim 3 wherein at least two of the distinct repeat units have differing numbers of fluorine atoms.
  - 5. The photoimageable composition of claim 3 wherein at least two of the distinct repeat units have differing numbers of silicon atoms.

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- 6. The photoimageable composition of claim 1 wherein the polymer comprises photoacid-labile groups.
- 7. The photoimageable composition of claim 1 wherein the composition is a negative-acting photoresist.
  - 8. The photoimageable composition of claim 1 wherein the polymer is substantially free of aromatic groups.

- 9. A coated substrate comprising:
- a) a polymer composition coating layer applied over a substrate surface;
- b) a coating layer of a photoimageable composition of claim 1 disposed over the polymer composition coating layer.

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- 10. A method for forming a electronic device, comprising:
- (a) applying on a substrate a coating layer of an organic polymer composition;
- (b) over the polymer composition coating layer, applying a photoimageable composition of claim 1;
  - (c) exposing the photoimageable composition coating layer to activating radiation and developing the exposed photoimageable layer.